

**POSITIVE RESIST COMPOSITION FOR ELECTRON BEAM OR X RAY**

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**Classification:**

**- international:** G03F7/039; G03F7/004; H01L21/027; G03F7/039;  
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**- European:**

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**Abstract of JP2002341538**

**PROBLEM TO BE SOLVED:** To provide a positive resist composition for electron beams or X rays having high sensitivity, high resolution and excellent stability of PED(post exposure delay). **SOLUTION:** The positive resist composition for electron beams or X rays contains (a) a compound which produces an acid by irradiation with electron beams or X rays, (b) a resin which increases the solubility to an alkali developer by the effect of an acid, (c) a low molecular weight compound stable against acid and having a residue of a compound showing the ionization potential (Ip) lower than the Ip of p-ethylphenol, and (d) a solvent.

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